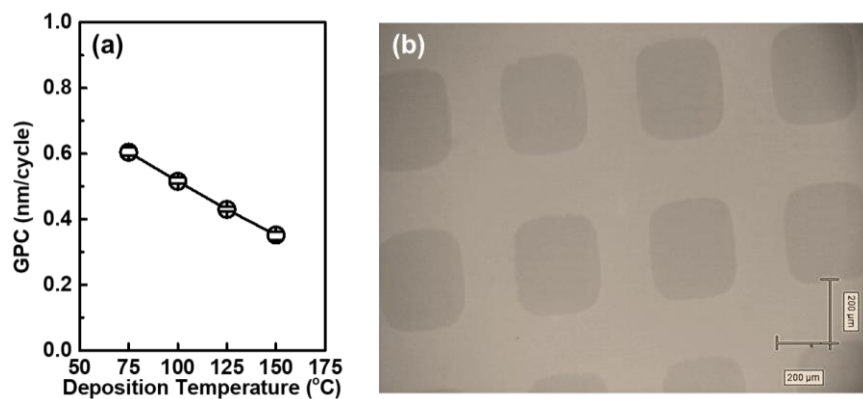


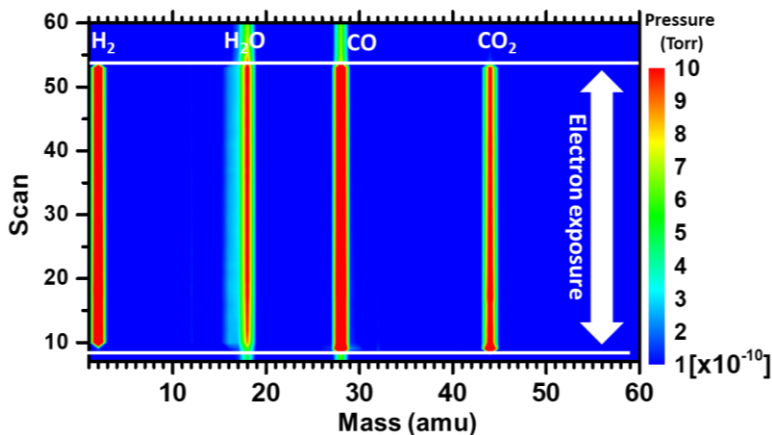
## ***Pushing the Boundaries: Advancing Resist Technology for Beyond EUV Lithography Application***

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Session – EM11: Emerging materials Poster Session



**Figure 1.** (a) The growth rate of Zn-based inorganic-organic hybrid thin films as a function of deposition temperature. (b) Optical image of 300×300 μm<sup>2</sup> patterns (post-development) achieved with Zn-based inorganic-organic hybrid thin films using 200 eV.



**Figure 2.** *in-operando* RGA spectrum during electron exposures, revealing H<sub>2</sub>, H<sub>2</sub>O, CO, and CO<sub>2</sub> are some of the byproducts formed.